

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
-	-	:	Examiner: NYA
HARUHITO ONO ET AL.			
		:	Group Art Unit: NYA
Application No.: 10/615,955)	
		:	
Filed: July 10, 2003)	
		:	
For:	MULTI-CHARGED BEAM LENS,)	
	CHARGED-PARTICLE BEAM	:	
	EXPOSURE APPARATUS USING)	
	THE SAME, AND DEVICE	:	
	MANUFACTURING METHOD)	September 2, 2003

Mail Stop Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed Form PTO-1449. Copies of the listed documents are also enclosed.

CONCLUSION

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

Attorney for Applicants

Registration No.

FITZPATRICK, CELLA, HARPER & SCINTO

30 Rockefeller Plaza

New York, New York 10112-3801

Facsimile: (212) 218-2200

367285V1

FORM PTO 1449 (modified)			ATTY DOCKET NO.		APPLICATION NO.	40/045 055				
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			00862.023131. 10/615,955 APPLICANT							
LIST OF REFERENCES CITED BY APPROANTIS			HARUHITO ONO ET AL.							
		FILING DATE JULY 10, 2003		0.3	GROUP NYA					
Date Submitted to PTO:[DATE] SEP 0 3 2003		U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL			NAME	CLASS		SUBCLASS	FILING DATE			
					·					
·										
·										
FOREIGN PATENT DOCUMENTS										
	DOCUMENT NUMBER	DATE	COUNTRY		CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT			
							i 			
							 			
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)										
T. Sasaki, A Multibeam Scheme for Electron-Beam Lithography, J. Vac. Sci. Technol., 19(4), Nov./Dec. 1981, pp. 963-965										
	K.Y. Lee et al., High Aspect Ratio Aligned Multilayer Microstructure Fabrication, J. Vac. Sci, Technol. B 12(6), Nov/Dec 1994, pp. 3425-3431									
	A.D. Feinerman, et al., Sub-centimeter Micromachined Electron Microscope, J. Vac. Sci. Technol. A 10(4), July/Aug 1992, pp 611-616									
EXAMINER			DATE CONSIDERED							

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.